## A Asenov

## List of Publications by Year in descending order

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253	4,938	27	63
papers	citations	h-index	g-index
259	259	259	2128
all docs	docs citations	times ranked	citing authors

#	Article	IF	CITATIONS
1	Random dopant induced threshold voltage lowering and fluctuations in sub-0.1 $1\frac{1}{4}$ m MOSFET's: A 3-D "atomistic" simulation study. IEEE Transactions on Electron Devices, 1998, 45, 2505-2513.	3.0	571
2	Intrinsic parameter fluctuations in decananometer mosfets introduced by gate line edge roughness. IEEE Transactions on Electron Devices, 2003, 50, 1254-1260.	3.0	525
3	Simulation of intrinsic parameter fluctuations in decananometer and nanometer-scale MOSFETs. IEEE Transactions on Electron Devices, 2003, 50, 1837-1852.	3.0	479
4	RTS amplitudes in decananometer MOSFETs: 3-D simulation study. IEEE Transactions on Electron Devices, 2003, 50, 839-845.	3.0	358
5	Increase in the random dopant induced threshold fluctuations and lowering in sub-100 nm MOSFETs due to quantum effects: a 3-D density-gradient simulation study. IEEE Transactions on Electron Devices, 2001, 48, 722-729.	3.0	198
6	Intrinsic threshold voltage fluctuations in decanano MOSFETs due to local oxide thickness variations. IEEE Transactions on Electron Devices, 2002, 49, 112-119.	3.0	162
7	Suppression of random dopant-induced threshold voltage fluctuations in sub-0.1-μm MOSFET's with epitaxial and δ-doped channels. IEEE Transactions on Electron Devices, 1999, 46, 1718-1724.	3.0	150
8	A Self-Consistent Full 3-D Real-Space NEGF Simulator for Studying Nonperturbative Effects in Nano-MOSFETs. IEEE Transactions on Electron Devices, 2007, 54, 2213-2222.	3.0	130
9	Intrinsic fluctuations in sub 10-nm double-gate MOSFETs introduced by discreteness of charge and matter. IEEE Nanotechnology Magazine, 2002, 1, 195-200.	2.0	88
10	Impact of intrinsic parameter fluctuations in decanano MOSFETs on yield and functionality of SRAM cells. Solid-State Electronics, 2005, 49, 740-746.	1.4	79
11	Quantitative Evaluation of Statistical Variability Sources in a 45-nm Technological Node LP N-MOSFET. IEEE Electron Device Letters, 2008, 29, 609-611.	3.9	75
12	Hierarchical approach to "atomistic" 3-D MOSFET simulation. IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems, 1999, 18, 1558-1565.	2.7	65
13	The impact of random doping effects on CMOS SRAM cell. , 0, , .		64
14	Polysilicon gate enhancement of the random dopant induced threshold voltage fluctuations in sub-100 nm MOSFETs with ultrathin gate oxide. IEEE Transactions on Electron Devices, 2000, 47, 805-812.	3.0	53
15	Complete Monte Carlo RF analysis of "real" short-channel compound FET's. IEEE Transactions on Electron Devices, 1998, 45, 1644-1652.	3.0	52
16	Scaling of pseudomorphic high electron mobility transistors to decanano dimensions. Solid-State Electronics, 2002, 46, 631-638.	1.4	52
17	Origin of the Asymmetry in the Magnitude of the Statistical Variability of n- and p-Channel Poly-Si Gate Bulk MOSFETs. IEEE Electron Device Letters, 2008, 29, 913-915.	3.9	46
18	High Mobility III-V MOSFETs For RF and Digital Applications. , 2007, , .		44

#	Article	IF	CITATIONS
19	Quantum corrections in the simulation of decanano MOSFETs. Solid-State Electronics, 2003, 47, 1141-1145.	1.4	43
20	Effective mobilities in pseudomorphic Si/SiGe/Si p-channel metal-oxide-semiconductor field-effect transistors with thin silicon capping layers. Applied Physics Letters, 2001, 78, 1424-1426.	3.3	42
21	The Use of Quantum Potentials for Confinement and Tunnelling in Semiconductor Devices. Journal of Computational Electronics, 2002, 1, 503-513.	2.5	39
22	Benchmarking of Scaled InGaAs Implant-Free NanoMOSFETs. IEEE Transactions on Electron Devices, 2008, 55, 2297-2306.	3.0	39
23	Simple approach to include external resistances in the Monte Carlo simulation of MESFETs and HEMTs. IEEE Transactions on Electron Devices, 1996, 43, 2032-2034.	3.0	36
24	Impact of Random Dopant Fluctuation on Bulk CMOS 6-T SRAM Scaling. Solid-State Device Research Conference, 2008 ESSDERC 2008 38th European, 2006, , .	0.0	35
25	Non-equilibrium Greenâ $\in$ <sup>TM</sup> s function analysis of cross section and channel length dependence of phonon scattering and its impact on the performance of Si nanowire field effect transistors. Journal of Applied Physics, 2011, 110, .	2.5	35
26	Modelling RTN and BTI in nanoscale MOSFETs from device to circuit: A review. Microelectronics Reliability, 2014, 54, 682-697.	1.7	35
27	CMOS 6-T SRAM cell design subject to "atomistic―fluctuations. Solid-State Electronics, 2007, 51, 565-571.	1.4	34
28	The impact of interface roughness scattering and degeneracy in relaxed and strained Si n-channel MOSFETs. Solid-State Electronics, 2004, 48, 1337-1346.	1.4	31
29	Impact of Single Charge Trapping in Nano-MOSFETs—Electrostatics Versus Transport Effects. IEEE Nanotechnology Magazine, 2005, 4, 339-344.	2.0	28
30	Advanced simulation of statistical variability and reliability in nano CMOS transistors., 2008,,.		28
31	3-D Nonequilibrium Green's Function Simulation of Nonperturbative Scattering From Discrete Dopants in the Source and Drain of a Silicon Nanowire Transistor. IEEE Nanotechnology Magazine, 2009, 8, 603-610.	2.0	27
32	Impact of interface state trap density on the performance characteristics of different Ill–V MOSFET architectures. Microelectronics Reliability, 2010, 50, 360-364.	1.7	27
33	Ballistic transport in Si, Ge, and GaAs nanowire MOSFETs., 0, , .		26
34	1â€[micro sign]m gate length, ln0.75Ga0.25As channel, thin body n-MOSFET on lnP substrate with transconductance of 737â€[micro sign]S/Î⅓m. Electronics Letters, 2008, 44, 498.	1.0	25
35	NEGF simulations of a junctionless Si gate-all-around nanowire transistor with discrete dopants. Solid-State Electronics, 2012, 71, 101-105.	1.4	25
36	Hot-carrier-induced deep-level defects from gated-diode measurements on MOSFETs. IEEE Electron Device Letters, 1990, 11, 95-97.	3.9	24

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37	Finite element Monte Carlo simulation of recess gate compound FFTs. Solid-State Electronics, 1996, 39, 629-635.	1.4	23
38	Random telegraph signal amplitudes in sub 100 nm (decanano) MOSFETs: a 3D 'Atomistic' simulation study. , 0, , .		23
39	Nanowire transistor solutions for 5nm and beyond. , 2016, , .		22
40	Oxide thickness variation induced threshold voltage fluctuations in decanano MOSFETs: a 3D density gradient simulation study. Superlattices and Microstructures, 2000, 28, 507-515.	3.1	21
41	Analysis of Statistical Fluctuations due to Line Edge Roughness in sub-0.1μm MOSFETs., 2001,, 78-81.		21
42	RC Variability of Short-Range Interconnects. , 2009, , .		20
43	Evaluation of statistical variability in 32 and 22nm technology generation LSTP MOSFETs. Solid-State Electronics, 2009, 53, 767-772.	1.4	20
44	Integrated atomistic process and device simulation of decananometre MOSFETs., 0,,.		19
45	Quantum mechanical enhancement of the random dopant induced threshold voltage fluctuations and lowering in sub 0.1 micron MOSFETs. , 0, , .		18
46	Monte Carlo simulations of III–V MOSFETs. Semiconductor Science and Technology, 2004, 19, S202-S205.	2.0	18
47	A comparison of advanced transport models for the computation of the drain current in nanoscale nMOSFETs. Solid-State Electronics, 2009, 53, 1293-1302.	1.4	18
48	Simulation based transistor-SRAM co-design in the presence of statistical variability and reliability. , 2013, , .		18
49	Impact of device geometry and doping strategy on linearity and RF performance in Si/SiGe MODFETs. Microelectronics Reliability, 2004, 44, 1101-1107.	1.7	17
50	Role of multiple delta doping in PHEMTs scaled to sub-100 nm dimensions. Solid-State Electronics, 2004, 48, 1223-1232.	1.4	16
51	Combined sources of intrinsic parameter fluctuations in sub-25nm generation UTB-SOI MOSFETs: A statistical simulation study. Solid-State Electronics, 2007, 51, 611-616.	1.4	16
52	Interplay between statistical reliability and variability: A comprehensive transistor-to-circuit simulation technology. , 2013, , .		16
53	Hot carrier aging and its variation under use-bias: Kinetics, prediction, impact on Vdd and SRAM. , 2015, , $\cdot$		16
54	Potential fluctuations in metal–oxide–semiconductor field-effect transistors generated by random impurities in the depletion layer. Journal of Applied Physics, 2002, 91, 4326-4334.	2.5	15

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55	Impact of scattering in â€~atomistic' device simulations. Solid-State Electronics, 2005, 49, 733-739.	1.4	15
56	Modeling and simulation of transistor and circuit variability and reliability. , 2010, , .		15
57	Simulation of direct source-to-drain tunnelling using the density gradient formalism: Non-Equilibrium Greens Function calibration. , 0, , .		14
58	Monte carlo simulations of sub-100 nm InGaAs MOSFETs for digital applications. , 0, , .		14
59	Impact of High- <l>κ</l> Gate Stacks on Transport and Variability in Nano-CMOS Devices. Journal of Computational and Theoretical Nanoscience, 2008, 5, 1072-1088.	0.4	14
60	Hot-carrier degradation monitoring in LDD n-MOSFETs using drain gated-diode measurements. Microelectronic Engineering, 1991, 15, 445-448.	2.4	13
61	PBTI/NBTI-Related Variability in TB-SOI and DG MOSFETs. IEEE Electron Device Letters, 2010, 31, 408-410.	3.9	13
62	Time-dependent variation: A new defect-based prediction methodology. , 2014, , .		13
63	Interaction between hot carrier aging and PBTI degradation in nMOSFETs: Characterization, modelling and lifetime prediction. , 2017, , .		13
64	Process Variability for Devices at and beyond the 7Ânm Node. ECS Journal of Solid State Science and Technology, 2018, 7, P595-P601.	1.8	12
65	Title is missing!. Journal of Computational Electronics, 2002, 1, 289-293.	2.5	11
66	Efficient three-dimensional parallel simulations of PHEMTs. International Journal of Numerical Modelling: Electronic Networks, Devices and Fields, 2005, 18, 327-340.	1.9	11
67	A study of the effect of the interface roughness on a DG-MOSFET using a full 2D NEGF technique. , 2005, , .		11
68	Key issues and techniques for characterizing time-dependent device-to-device variation of SRAM. , 2013, , .		11
69	Electron dynamics in nanoscale transistors by means of Wigner and Boltzmann approaches. Physica A: Statistical Mechanics and Its Applications, 2014, 398, 194-198.	2.6	11
70	Thorough Understanding of Retention Time of Z2FET Memory Operation. IEEE Transactions on Electron Devices, 2019, 66, 383-388.	3.0	11
71	Strain engineered pHEMTs on virtual substrates: a Monte Carlo simulation study. Solid-State Electronics, 1999, 43, 1281-1288.	1.4	10
72	Effect of oxide interface roughness on the threshold voltage fluctuations in decanano MOSFETs with ultrathin gate oxides. , 0, , .		10

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73	Intrinsic parameter fluctuations in MOSFETs due to structural non-uniformity of high-/spl kappa/ gate stack materials. , 2005, , .		10
74	Simulation of combined sources of intrinsic parameter fluctuations in a 'real' 35 nm MOSFET., 0, , .		10
75	Integrating intrinsic parameter fluctuation description into BSIMSOI to forecast sub-15nm UTB SOI based 6T SRAM operation. Solid-State Electronics, 2006, 50, 86-93.	1.4	10
76	Impact of Intrinsic Parameter Fluctuations on SRAM Cell Design. , 2006, , .		10
77	Beyond SiO2 technology: Simulation of the impact of high-Î <sup>º</sup> dielectrics on mobility. Journal of Non-Crystalline Solids, 2007, 353, 630-634.	3.1	10
78	Statistical Compact Model Parameter Extraction Strategy for Intrinsic Parameter Fluctuation. , 2007, , 301-304.		10
79	Impact of intrinsic parameter fluctuations on the performance of HEMTs studied with a 3D parallel drift-diffusion simulator. Solid-State Electronics, 2007, 51, 481-488.	1.4	10
80	Parameter set and data sampling strategy for accurate yet efficient statistical MOSFET compact model extraction. Solid-State Electronics, 2010, 54, 307-315.	1.4	10
81	Speed-up of scalable iterative linear solvers implemented on an array of transputers. Parallel Computing, 1994, 20, 375-387.	2.1	9
82	Impact of high-/spl kappa/ dielectric HfO/sub 2/ on the mobility and device performance of sub-100-nm nMOSFETs. IEEE Transactions on Device and Materials Reliability, 2005, 5, 103-108.	2.0	9
83	Intrinsic parameter fluctuations in conventional MOSFETs until the end of the ITRS: A statistical simulation study. Journal of Physics: Conference Series, 2006, 38, 188-191.	0.4	9
84	Monte Carlo simulations of InGaAs nano-MOSFETs. Microelectronic Engineering, 2007, 84, 2150-2153.	2.4	9
85	A Comparison between a Fully-3D Real-Space Versus Coupled Mode-Space NEGF in the Study of Variability in Gate-All-Around Si Nanowire MOSFET. , 2009, , .		9
86	Impact of random dopant fluctuations on trap-assisted tunnelling in nanoscale MOSFETs. Microelectronics Reliability, 2012, 52, 1918-1923.	1.7	9
87	MS-EMC vs. NEGF: A comparative study accounting for transport quantum corrections. , 2018, , .		9
88	Scalable parallel 3D finite element nonlinear poisson solver. Simulation Modelling Practice and Theory, 1996, 4, 155-168.	0.3	8
89	Effect of single-electron interface trapping in decanano MOSFETs: A 3D atomistic simulation study. Superlattices and Microstructures, 2000, 27, 411-416.	3.1	8
90	Nonequilibrium transport in scaled high electron mobility transistors. Semiconductor Science and Technology, 2002, 17, 579-584.	2.0	8

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91	Intrinsic fluctuations induced by a high- $\hat{l}^2$ gate dielectric in sub-100 nm Si MOSFETs. AIP Conference Proceedings, 2005, , .	0.4	8
92	Modelling of InP HEMTs with high indium content channels., 0,,.		8
93	Simulation of implant free III-V MOSFETs for high performance low power Nano-CMOS applications. Microelectronic Engineering, 2007, 84, 2398-2403.	2.4	8
94	Effect of interface state trap density on the characteristics of n-type, enhancement-mode, implant-free In0.3Ga0.7As MOSFETs. Microelectronic Engineering, 2009, 86, 1564-1567.	2.4	8
95	A novel approach to the statistical generation of non-normal distributed PSP compact model parameters using a nonlinear power method. , 2010, , .		8
96	Combining process and statistical variability in the evaluation of the effectiveness of corners in digital circuit parametric yield analysis. , $2010$ , , .		8
97	New evidence for velocity overshoot in a 200 nm pseudomorphic HEMT. Microelectronics Journal, 1996, 27, 785-793.	2.0	7
98	Ab-initio Coulomb Scattering in Atomistic Device Simulation. VLSI Design, 1998, 8, 331-335.	0.5	7
99	Degeneracy and High Doping Effects in Deep Sub-Micron Relaxed and Strained Si n-MOSFETs. Journal of Computational Electronics, 2003, 2, 475-479.	2.5	7
100	Interface roughness scattering and its impact on electron transport in relaxed and strained Si n-MOSFETs. Semiconductor Science and Technology, 2004, 19, S155-S157.	2.0	7
101	Sub-25nm UTB SOI SRAM cell under the influence of discrete random dopants. Solid-State Electronics, 2006, 50, 660-667.	1.4	7
102	On the impact of high- $\hat{l}^2$ gate stacks on mobility: A Monte Carlo study including coupled SO phonon-plasmon scattering. Journal of Computational Electronics, 2007, 6, 1-5.	2.5	7
103	Modelling circuit performance variations due to statistical variability: Monte Carlo static timing analysis., 2011,,.		7
104	RTN distribution comparison for bulk, FDSOI and FinFETs devices. Microelectronics Reliability, 2014, 54, 1749-1752.	1.7	7
105	Unified approach for simulation of statistical reliability in nanoscale CMOS transistors from devices to circuits. , $2015, \dots$		7
106	On the nature and energy distribution of defect states caused by hot electrons in Si. Applied Surface Science, 1987, 30, 319-324.	6.1	6
107	UTB SOI SRAM cell stability under the influence of intrinsic parameter fluctuation., 0,,.		6
108	A study of the interface roughness effect in Si nanowires using a full 3D NEGF approach. Physica E: Low-Dimensional Systems and Nanostructures, 2007, 37, 168-172.	2.7	6

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109	Developing a full 3D NEGF simulator with random dopant and interface roughness. Journal of Computational Electronics, 2007, 6, 215-218.	2.5	6
110	Evaluation of intrinsic parameter fluctuations on 45, 32 and 22nm technology node LP N-MOSFETs. , 2008, , .		6
111	Dopants and roughness induced resonances in thin Si nanowire transistors: A self-consistent NEGF-poisson study. Journal of Physics: Conference Series, 2010, 220, 012009.	0.4	6
112	Enriched residual free bubbles for semiconductor device simulation. Computational Mechanics, 2012, 50, 119-133.	4.0	6
113	Study of the 1D Scattering Mechanisms' Impact on the Mobility in Si Nanowire Transistors. , 2018, , .		6
114	Statistical 3D â€~atomistic' simulation of decanano MOSFETs. Superlattices and Microstructures, 2000, 27, 215-227.	3.1	5
115	Scaling of pHEMTs to Decanano Dimensions. VLSI Design, 2001, 13, 435-439.	0.5	5
116	Quantum Corrections to the â€~Atomistic' MOSFET Simulations. VLSI Design, 2001, 13, 15-21.	0.5	5
117	Excessive Over-Relaxation Method for Multigrid Poisson Solvers. Journal of Computational Electronics, 2002, 1, 341-345.	2.5	5
118	Brownian Ionic Channel Simulation. Journal of Computational Electronics, 2003, 2, 257-262.	2.5	5
119	3D Parallel Simulations of Fluctuation Effects in pHEMTs. Journal of Computational Electronics, 2003, 2, 369-373.	2.5	5
120	A Methodology for Quantitatively Introducing †Atomistic†Fluctuations into Compact Device Models for Circuit Analysis. Journal of Computational Electronics, 2003, 2, 427-431.	2.5	5
121	Green function study of quantum transport in ultra-small devices with embedded atomistic clusters. Journal of Physics: Conference Series, 2006, 35, 233-246.	0.4	5
122	The scalability of 8T-SRAM cells under the influence of intrinsic parameter fluctuations. Solid-State Circuits Conference, 2008 ESSCIRC 2008 34th European, 2007, , .	0.0	5
123	Brownian simulation of charge transport in $\hat{l}$ ±-Haemolysin. Journal of Computational Electronics, 2008, 7, 28-33.	2.5	5
124	Secure, Performance-Oriented Data Management for nanoCMOS Electronics. , 2008, , .		5
125	NEGF simulations of a junctionless Si gate-all-around nanowire transistor with discrete dopants. , 2011, , .		5
126	Statistical aspects of NBTI/PBTI and impact on SRAM yield. , 2011, , .		5

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127	An advanced statistical compact model strategy for SRAM simulation at reduced V <inf>DD</inf> . , 2012, , .		5
128	A physics-based investigation of Pt-salt doped carbon nanotubes for local interconnects. , 2017, , .		5
129	Statistically reliable â€~Atomistic' Simulation of Sub 100 nm MOSFETs. , 1998, , 223-226.		5
130	Gender neutral engineering: an impossible dream? ―the case of Eastern Europe. International Journal of Science Education, 1998, 20, 783-793.	1.9	4
131	Topologically Rectangular Grids in the Parallel Simulation of Semiconductor Devices. VLSI Design, 1998, 6, 91-95.	0.5	4
132	Transconductance, carrier mobility and 1/f noise in Si/Si0.64Ge0.36/Si pMOSFETs. Materials Science and Engineering B: Solid-State Materials for Advanced Technology, 2002, 89, 444-448.	3.5	4
133	Quantum mechanical and transport aspects of resolving discrete charges in nano-CMOS device simulation. , 0, , .		4
134	A NEGF study of the effect of surface roughness on CMOS nanotransistors. Journal of Physics: Conference Series, 2006, 35, 269-274.	0.4	4
135	Study of fluctuations in advanced MOSFETs using a 3D finite element parallel simulator. Journal of Computational Electronics, 2007, 5, 311-314.	2.5	4
136	Random dopant related variability in the 30Ânm gate length In0.75Ga0.25As implant free MOSFET. Journal of Computational Electronics, 2008, 7, 159-163.	2.5	4
137	Simulation of impurities with an attractive potential in fully 3-D real-space Non-Equilibrium Green's Function quantum transport simulations., 2008,,.		4
138	Benchmarking the Accuracy of PCA Generated Statistical Compact Model Parameters Against Physical Device Simulation and Directly Extracted Statistical Parameters. , 2009, , .		4
139	The effect of compact modelling strategy on SNM and Read Current variability in Modern SRAM. , $2011$ , , $\cdot$		4
140	Assessment of gate leakage mechanism utilizing Multi-Subband Ensemble Monte Carlo. , 2017, , .		4
141	Efficient hole transport model in warped bands for use in the simulation of Si/SiGe MOSFETs., 0, , .		3
142	Mesh-based particle simulation of sub-0.1 micron FETs. Semiconductor Science and Technology, 1998, 13, A173-A176.	2.0	3
143	Efficient 3D 'atomistic' simulation technique for studying of random dopant induced threshold voltage lowering and fluctuations in decanano MOSFETs. , 0, , .		3
144	RF analysis of aggressively scaled pHEMTs. , 2000, , .		3

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145	Scaling study of Si/SiGe MODFETs for RF applications. , 0, , .		3
146	Implications of Imperfect Interfaces and Edges in Ultra-small MOSFET Characteristics. Physica Status Solidi (B): Basic Research, 2002, 233, 101-112.	1.5	3
147	Generic Particle-Mesh Framework for the Simulation of Ionic Channels. Journal of Computational Electronics, 2002, 1, 405-409.	2.5	3
148	Scattering from Body Thickness Fluctuations in Double Gate MOSFETs: An ab initio Monte Carlo Simulation Study. Journal of Computational Electronics, 2004, 3, 341-345.	2.5	3
149	Monte carlo study of mobility in Si devices with -based oxides. Materials Science in Semiconductor Processing, 2006, 9, 995-999.	4.0	3
150	Atomistic effect of delta doping layer in a 50 nm InP HEMT. Journal of Computational Electronics, 2006, 5, 131-135.	2.5	3
151	Statistical study of the effect of interface charge fluctuations in HEMTs using a 3D simulator. Journal of Computational Electronics, 2007, 5, 385-388.	2.5	3
152	A full 3D non-equilibrium Green functions study of aÂstray charge inÂaÂnanowire MOS transistor. Journal of Computational Electronics, 2008, 7, 359-362.	2.5	3
153	Integrating Security Solutions to Support nanoCMOS Electronics Research., 2008,,.		3
154	Atomistic mesh generation for the simulation of nanoscale metal-oxide-semiconductor field-effect transistors. Physical Review E, 2008, 77, 056702.	2.1	3
155	Monte Carlo analysis of In <inf>0.53</inf> Ga <inf>0.47</inf> as Implant-Free Quantum-Well device performance. , 2010, , .		3
156	Capturing intrinsic parameter fluctuations using the PSP compact model. , 2010, , .		3
157	Monte Carlo simulation study of hole mobility in germanium MOS inversion layers. , 2010, , .		3
158	Simulation study of the 20nm gate-length Ge implant-free quantum well p-MOSFET. Microelectronic Engineering, 2011, 88, 362-365.	2.4	3
159	Quantum insights in gate oxide charge-trapping dynamics in nanoscale MOSFETs. , 2013, , .		3
160	3D electro-thermal simulations of bulk FinFETs with statistical variations. , 2015, , .		3
161	Speed-up of scalable iterative linear solvers implemented on an array of transputers. Parallel Computing, 1995, 21, 669-682.	2.1	2
162	Parallel semiconductor device simulation: from power to 'atomistic' devices. , 0, , .		2

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163	Effect of impact ionization in scaled pHEMTs., 0,,.		2
164	Multiple delta doping in aggressively scaled PHEMTs., 2001,,.		2
165	High performance III-V MOSFETs: a dream close to reality?. , 0, , .		2
166	Breakdown of universal mobility curves in sub-100-nm MOSFETs. IEEE Nanotechnology Magazine, 2002, 1, 260-264.	2.0	2
167	Quantum Corrections in the Monte Carlo Simulations of Scaled PHEMTs with Multiple Delta Doping. Journal of Computational Electronics, 2002, 1, 257-261.	2.5	2
168	Simulation Study of High Performance III-V MOSFETs for Digital Applications. Journal of Computational Electronics, 2003, 2, 341-345.	2.5	2
169	Applicability of Quasi-3D and 3D MOSFET Simulations in the â€~Atomistic' Regime. Journal of Computational Electronics, 2003, 2, 423-426.	2.5	2
170	Artificial carrier heating due to the introduction of ab initio Coulomb scattering in Monte Carlo simulations. Superlattices and Microstructures, 2003, 34, 319-326.	3.1	2
171	Self-aligned 0.12 μm T-gate In/sub .53/Ga/sub .47/As/In/sub .52/Al/sub .48/As HEMT technology utilising a non-annealed ohmic contact strategy. , 0, , .		2
172	Simulations of Sub-100 nm Strained Si MOSFETs with High-κ Gate Stacks. Journal of Computational Electronics, 2004, 3, 171-175.	2.5	2
173	Simulating the bio-nano-CMOS interface. , 0, , .		2
174	Development of a Full 3D NEGF Nano-CMOS Simulator. , 2006, , .		2
175	Current variations in PHEMTS introduced by channel composition fluctuations. Journal of Physics: Conference Series, 2006, 38, 212-215.	0.4	2
176	Monte Carlo Simulation of Implant Free InGaAs MOSFET. Journal of Physics: Conference Series, 2006, 38, 200-203.	0.4	2
177	Introducing energy broadening in semiclassical Monte Carlo simulations. Journal of Computational Electronics, 2007, 5, 419-423.	2.5	2
178	Impact of intrinsic parameter fluctuations on the performance of In <sub>0.75</sub> Ga <sub>0.25</sub> As implant free MOSFETs. Semiconductor Science and Technology, 2009, 24, 055011.	2.0	2
179	Impact of the field induced polarization space-charge on the characteristics of AlGaN/GaN HEMT: Self-consistent simulation study. Physica Status Solidi C: Current Topics in Solid State Physics, 2009, 6, S1007-S1011.	0.8	2
180	Effect of interface state trap density on the performance of scaled surface channel In <sub>0.3</sub> Ga <sub>0.7</sub> As MOSFETs. Journal of Physics: Conference Series, 2009, 193, 012122.	0.4	2

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181	FET based nano-pore sensing: a 3D simulation study. Journal of Computational Electronics, 2012, 11, 266-271.	2.5	2
182	Silicon-on-insulator (SOI) fin-on-oxide field effect transistors (FinFETs)., 2014, , 195-211.		2
183	Challenges and Progress on Carbon Nanotube Integration for BEOL Interconnects. , 2018, , .		2
184	Simulation of Statistical NBTI Degradation in 10nm Doped Channel pFinFETs., 2019,,.		2
185	MOSFETs Under Electrical Stress â€" Degradation, Subthreshold Conduction, and Noise in a Submicron Structure. Springer Series in Solid-state Sciences, 1988, , 253-262.	0.3	2
186	A Combined First Principles and Kinetic Monte Carlo study of Polyoxometalate based Molecular Memory Devices. , $2020$ , , .		2
187	Simulation of Nano-CMOS Devices: From Atoms to Architecture. Nanostructure Science and Technology, 2007, , 257-303.	0.1	2
188	Ultra-linear pseudomorphic HEMTs for wireless communications: A simulation study., 1997,,.		1
189	Monte Carlo Analysis of Si/SiGe MODFET Performance Potential. Physica Status Solidi (B): Basic Research, 1997, 204, 525-527.	1.5	1
190	RF analysis methodology for Si and SiGe FETs based on transient Monte Carlo simulation. , 0, , .		1
191	Scaling of pHEMTs to decanano dimensions. , 0, , .		1
192	Quantum corrections to the 'atomistic' MOSFET simulation. , 0, , .		1
193	Gate tunnelling and impact ionisation in sub 100 nm PHEMTs., 0,,.		1
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